

<b>Notice of References Cited</b>	Application/Control No. 10/719,083		Applicant(s)/Patent Under Reexamination HWANG ET AL.	
	Examiner Patricia A. George		Art Unit 1765	Page 1 of 3

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,692,892	02-2004	Takano et al.	430/270.1
*	B	US-6,190,824	02-2001	Fukushige et al.	430/163
*	C	US-6,261,721	07-2001	Andrieu et al.	429/249
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	J. Meute of IBM "157nm Stepper Optics Lifetime Field Experience" presentation at Semitech - Dec. 2001
*	V	Shibata et al. of Material and Process Development of Tri-level Resist System in KrF and ArF Lithography [Proc. SPIE Vol. 4690, July 2002, Advances in Resist Technology and Processing XIX;
*	W	Meador et al. (193-nm Multilayer Imaging Systems; Proc. SPIE Vol. 5039, June 2003, Advances in Resist Technology and Processing XX; Theodore H. Fedynyshyn; Ed.)
*	X	Samoc et al. "PHOTOPHYSICAL PROCESSES INVOLVED IN CREATION OF DARK SPATIAL SOLITONS IN COMPOSITE PHOTONIC MEDIA", Laser Physics Centre, Australian National University, Canberra, ACT 0200, Au, 1993; 5420197; 6306439

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.